Tommaso Jacopo Giammaria

List of Publications by Year in descending order

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27 papers 670 citations

471509 17 h-index 25 g-index

27 all docs

27 docs citations

times ranked

27

541 citing authors

#	Article	IF	Citations
1	Influence of spin casting solvent on the selfâ€assembly of siliconâ€containing block copolymer thin films via high temperature thermal treatment. Polymer International, 2022, 71, 426-435.	3.1	3
2	Resist-Free Directed Self-Assembly Chemo-Epitaxy Approach for Line/Space Patterning. Nanomaterials, 2020, 10, 2443.	4.1	1
3	Effect of Trapped Solvent on the Interface between PS- <i>b</i> -PMMA Thin Films and P(S- <i>r</i> -MMA) Brush Layers. ACS Applied Materials & Description of the Interfaces, 2020, 12, 7777-7787.	8.0	21
4	Spacer patterning lithography as a new process to induce block copolymer alignment by chemo-epitaxy. , 2019, , .		2
5	Technological strategies for self-assembly of PS-b-PDMS in cylindrical sub-10 nm nanostructures for lithographic applications. Advances in Physics: X, 2018, 3, 1445558.	4.1	6
6	Hierarchical Order in Dewetted Block Copolymer Thin Films on Chemically Patterned Surfaces. ACS Nano, 2018, 12, 7076-7085.	14.6	22
7	Effect of Entrapped Solvent on the Evolution of Lateral Order in Self-Assembled P(S- <i>r</i> -MMA)/PS- <i>b</i> -PMMA Systems with Different Thicknesses. ACS Applied Materials & Interfaces, 2017, 9, 31215-31223.	8.0	15
8	GISAXS Analysis of the In-Depth Morphology of Thick PS- <i>b</i> -PMMA Films. ACS Applied Materials & Lamp; Interfaces, 2017, 9, 11054-11063.	8.0	24
9	High temperature surface neutralization process with random copolymers for block copolymer selfâ€assembly. Polymer International, 2017, 66, 459-467.	3.1	21
10	Molar mass and composition effects on the thermal stability of functional P(S- <i>r</i> -MMA) random copolymers for nanolithographic applications. Molecular Systems Design and Engineering, 2017, 2, 581-588.	3.4	4
11	Micrometer-Scale Ordering of Silicon-Containing Block Copolymer Thin Films via High-Temperature Thermal Treatments. ACS Applied Materials & Interfaces, 2016, 8, 9897-9908.	8.0	19
12	Surface engineering with functional random copolymers for nanolithographic applications. AIP Conference Proceedings, 2016, , .	0.4	1
13	Neutral wetting brush layers for block copolymer thin films using homopolymer blends. AIP Conference Proceedings, 2016, , .	0.4	0
14	Composition of ultrathin binary polymer brushes by thermogravimetry–gas chromatography–mass spectrometry. Analytical and Bioanalytical Chemistry, 2016, 408, 3155-3163.	3.7	6
15	Enhanced Lateral Ordering in Cylinder Forming PS- <i>b</i> brPMMA Block Copolymers Exploiting the Entrapped Solvent. ACS Applied Materials & Entrapped Solvent & Entrapped Solvent & Entrapped Solv	8.0	22
16	Thickness and Microdomain Orientation of Asymmetric PS- <i>b</i> -PMMA Block Copolymer Films Inside Periodic Gratings. ACS Applied Materials & Description (2015), 7, 23615-23622.	8.0	11
17	Thermal Stability of Functional P(S-r-MMA) Random Copolymers for Nanolithographic Applications. ACS Applied Materials & Distributions (2015, 7, 3920-3930).	8.0	28
18	Ultrathin Random Copolymer-Grafted Layers for Block Copolymer Self-Assembly. ACS Applied Materials & 2015, 7, 10944-10951.	8.0	71

#	Article	IF	CITATIONS
19	High Aspect Ratio PS- <i>b</i> -PMMA Block Copolymer Masks for Lithographic Applications. ACS Applied Materials & Samp; Interfaces, 2014, 6, 21389-21396.	8.0	35
20	Thermally induced self-assembly of cylindrical nanodomains in low molecular weight PS- <i>b</i> -PMMA thin films. Nanotechnology, 2014, 25, 045301.	2.6	31
21	Thermally induced orientational flipping of cylindrical phase diblock copolymers. Journal of Materials Chemistry C, 2014, 2, 2175-2182.	5.5	20
22	Characterization of ultra-thin polymeric films by Gas chromatography-Mass spectrometry hyphenated to thermogravimetry. Journal of Chromatography A, 2014, 1368, 204-210.	3.7	31
23	Ordering dynamics in symmetric PS-b-PMMA diblock copolymer thin films during rapid thermal processing. Journal of Materials Chemistry C, 2014, 2, 6655-6664.	5.5	54
24	Flash grafting of functional random copolymers for surface neutralization. Journal of Materials Chemistry C, 2014, 2, 4909-4917.	5.5	43
25	Fine Tuning of Lithographic Masks through Thin Films of PS- <i>b</i> -PMMA with Different Molar Mass by Rapid Thermal Processing. ACS Applied Materials & Samp; Interfaces, 2014, 6, 7180-7188.	8.0	64
26	On the Thermal Stability of PS- <i>b</i> -PMMA Block and P(S- <i>r</i> -MMA) Random Copolymers for Nanopatterning Applications. Macromolecules, 2013, 46, 8224-8234.	4.8	43
27	Rapid thermal processing of self-assembling block copolymer thin films. Nanotechnology, 2013, 24, 315601.	2.6	72